

# PVD 75™

## Thin Film Deposition System



**Kurt J. Lesker®**  
Company

**PROCESS EQUIPMENT™**  
DIVISION

### Applications

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- Designed for university, industrial, and government lab R&D thin film deposition
- OLED/PLED and organic electronics applications
- Photovoltaics and semiconductor devices
- Optics and decorative coatings
- Small batch production

### Features

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- Fully enclosed “zero” clean room footprint or optional open frame design
- D-shape 304 stainless steel chamber with aluminum door and large viewport
- Manual touch-screen or recipe-controlled, PC based process automation
- Turbomolecular or optional cryogenic high vacuum pumping

### Process Modules

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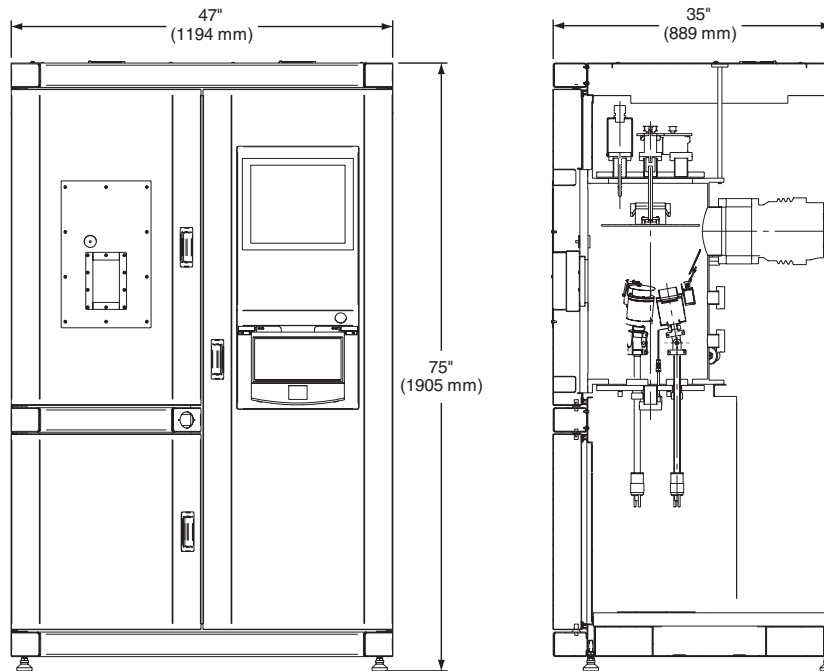
- Magnetron sputtering: RF, DC, Pulsed DC
- Electron beam evaporation
- Thermal evaporation
- Organic materials evaporation
- Ion source substrate cleaning or assisted deposition

### Options

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- Substrate heating, cooling, or biasing
- Planetary substrate fixturing
- Upstream or downstream pressure control
- Film thickness control
- Substrate load lock
- On-site installation and training

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Dimensions Approximate

## Specifications

Process Chamber Volume	75 liters
Process Chamber Geometry	D-Shaped, 14" (365mm) wide X 14" deep (365mm) X 24" (610mm) high
Process Chamber Construction	304L Stainless Steel with 6061 Aluminum Hinged Door
Cabinet Construction	Carbon Steel, Fully Enclosed, Gray Powder Coat Finish
Deposition Sources (Available in various combinations)	Torus® Magnetron Sputtering Cathode
	4-Pocket 8cc Electron Beam Source
	Multiple Boat Source Thermal Evaporation
	LTE Organic Material Evaporation Source
Deposition Orientation	Sputter Up or Down, Evaporation Up
Substrate Cleaning	Ion Source or RF Bias
Substrate Size (max)	Single 12" (300mm) with optional 20 RPM max variable rotation
Substrate Heating	Quartz Lamp or Resistive Element
Standard Vacuum Pumping	260 l/sec Turbo Pump, Optional 685 l/sec Turbo Pump, or 1500 l/sec Cryo Pump Available
Gauging	Wide Range Vacuum Gauge
Base Pressure Turbo Pump (CDE)	$5 \times 10^{-7}$ Torr ( $6.7 \times 10^{-7}$ mbar)
Process Gas	2 Channel Manual with Optional Mass Flow Control with Pressure Control
System Control	PC-Based HMI, with optional Recipe Control and Datalogging
Required Power (typical, based on options)	208VAC, 3Ø, 50/60 Hz; Optional 380VAC, 3Ø, 50/60 Hz
Available Certifications, Markings	CE and CSA
Warranty	12 months upon shipment
Overall Dimensions (approx)	47" (1194mm) wide X 35" (889mm) deep X 75" (1905mm) high
Weight (approx)	1,800 lbs (816 kg)

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